## AMENDMENTS TO THE CLAIMS

Claims 1-169 (Canceled)

- 170. (currently amended) A semiconductor component comprising:
- a thinned semiconductor die having an outline, a circuit side, a planarized back side, four peripheral edges, and a plurality of die contacts on the circuit side;
  - a plurality of contact bumps on the die contacts;
- a planarized first polymer layer comprising a self planarizing thermoset underfill film covering the circuit side, the contact bumps and the peripheral edges, the first polymer layer having a first planar surface and edge polymer layers covering and rigidifying the peripheral edges; and
- a <del>planarized</del> second polymer layer covering the back side <u>having a second planar</u> surface.

the first polymer layer and the second polymer layer encapsulating the die on six sides and supporting the die, the contact bumps and the peripheral edges. such that the component has a chip scale outline corresponding to the outline of the die plus the edge polymer layers; and

a plurality of terminal contacts on the contact bumps.

- 171. (previously presented) The semiconductor component of claim 170 wherein the die comprises a tested and burned in die and the component comprises a known good component (KGC).
- 172. (currently amended). The semiconductor component of claim 170 wherein the <u>underfill film cures and planarizes at a temperature of about 200-250 °C, has a Young's modulus of about 4G Pascal, and a coefficient of thermal expansion (CTE) of about 33 parts per million per °C.</u>

contact bumps comprise metal bumps in a dense area array.

- 173. (currently amended) The semiconductor component of claim 170 wherein the second polymer layer comprises the underfill film.

  terminal contacts comprise conductive bumps or balls in a grid array.
- 174. (currently amended) The semiconductor component of claim 170 wherein the <u>first polymer layer and the second polymer layer have beveled edges.</u>

first polymer layer and the contact bumps have a same planar surface.

175. (currently amended) The semiconductor component of claim 170 <u>further</u> comprising a plurality of terminal contacts on the contact bumps.

wherein the second polymer layer covers planarized edges of the edge polymer layers.

176. (currently amended) The semiconductor component of claim 170 wherein the first polymer layer has a thickness which is less than a height of the contact bumps and each contact bump is surrounded by a portion of the first polymer layer. further comprising a plurality of conductive vias in the thinned die in electrical communication with the die contacts and with the terminal contacts.

177. (currently amended) The semiconductor component of claim <u>170 wherein</u> the die includes conductive vias in electrical communication with the die contacts and the contact bumps.

176 further comprising a plurality of second die contacts on the second polymer layer in electrical communication with the conductive vias.

178. (currently amended) The semiconductor component of claim 170 wherein the <u>die contacts comprise bond pads</u>. second polymer layer comprises a photopolymer.

179. (currently amended) The semiconductor component of claim 170 wherein the <u>die contacts comprise redistribution pads.</u>
second polymer layer comprises a wafer level underfill.

Claims 180-261 (canceled)

- 262. (currently amended) The semiconductor component of claim 170 wherein the <u>die contacts comprise a solderable metal</u>, and the contact bumps comprise solder. eontact bumps comprise planarized surfaces.
- 263. (currently amended) The semiconductor component of claim 170 <u>further comprising a plurality of terminal contacts on the die in electrical communication with the contact bumps in a standardized grid array.</u>

wherein the backside comprises a polished surface.

- 264. (currently amended) The semiconductor component of claim 170 <u>further</u> comprising a plurality of terminal contacts comprising ball bonds on the contact bumps. wherein the second polymer layer comprises a tape material.
- 265. (previously presented) The semiconductor component of claim 170 wherein the first polymer layer on each edge comprises a portion of a polymer filled trench.
- 266. (previously presented) The semiconductor component of claim 170 wherein the edge polymer layers and the back side have a same planar surface.
- 267. (previously presented) The semiconductor component of claim 170 wherein the edge polymer layers have a selected thickness which is different than a thickness of the first polymer layer.
- 268. (currently amended) The semiconductor component of claim 170 wherein the thinned die comprises a tested and burned in die.
- 269. (currently amended) The semiconductor component of claim 170 wherein the thinned die is contained on a semiconductor wafer having a polymer support dam proximate to edges thereof.
- 270. (currently amended) The semiconductor component of claim 170 wherein the first polymer layer comprises a first polymer material and the second polymer layer comprises the underfill film, and the underfill film cures and planarizes at a temperature of about 200-250 °C, has a Young's modulus of about 4G Pascal, and a coefficient of thermal expansion (CTE) of about 33 parts per million per °C.

## a second polymer material

271. (currently amended) The semiconductor component of claim 170 wherein the first second polymer layer comprises parylene.

Claim 272 (canceled)